

<b>INFORMATION DISCLOSURE STATEMENT</b> <b>IN AN APPLICATION</b> (Use several sheets if necessary) PTO Form 1449	Atty Docket No. 112857-319	Application No. 10/092,687
	Applicant Hiroyuki Okuyama et al.	
	Filing Date 03/06/2002	Group 2822

### U.S. PATENT DOCUMENTS

Examiner's Initials	Document Number	Publication Date	Inventor	Class	Subclass	Filing Date If Appropriate
MP	5,177,405	01/05/1993	Kusuda et al.	—	—	—
MP	5,981,977	11/09/1999	Furukawa et al.	—	—	—

### FOREIGN PATENT DOCUMENTS

Examiner's Initials	Document Number	Publication Date	Country	Class	Subclass	Translation	
						Yes	No
MP	✓ 56-92577	07/27/1981	Japan	—	—	—	✓
MP	✓ 57-45583	03/15/1982	Japan	—	—	—	✓
MP	✓ 57-52071	03/27/1982	Japan	—	—	—	✓
MP	✓ 57-52072	03/27/1982	Japan	—	—	—	✓
MP	✓ 57-52073	03/27/1982	Japan	—	—	—	✓
MP	✓ 58-50577	03/25/1983	Japan	—	—	—	✓
MP	✓ 61-156780	07/16/1986	Japan	—	—	—	✓
MP	✓ 63-188938	08/04/1988	Japan	—	—	—	✓
MP	✓ 64-149491	06/12/1989	Japan	—	—	—	✓
MP	✓ 72-263668	10/26/1990	Japan	—	—	—	✓
MP	✓ 83-035568	02/15/1991	Japan	—	—	—	✓
MP	✓ 84-45648	02/18/1994	Japan	—	—	—	✓
MP	✓ 86-067044	03/11/1994	Japan	—	—	—	✓
MP	✓ 87-199829	04/08/1995	Japan	—	—	—	✓
MP	✓ 87-283438	10/27/1995	Japan	—	—	—	✓
MP	✓ 88-008217	01/12/1996	Japan	—	—	—	✓
MP	✓ 88-274376	10/18/1996	Japan	—	—	—	✓
MP	✓ 91-129974	05/16/1997	Japan	—	—	—	✓
MP	✓ 99-274455	10/21/1997	Japan	—	—	—	✓
MP	✓ WO 97/44612	11/27/1997	PCT	—	—	—	✓
MP	✓ 10-125929	05/05/1998	Japan	—	—	—	✓
MP	✓ 10-270801	10/09/1998	Japan	—	—	—	✓
MP	✓ 10-312971	11/24/1998	Japan	—	—	—	✓
MP	✓ 11-26883	01/29/1999	Japan	—	—	—	✓

Examiner: *[Signature]*

Date Considered: 9/04

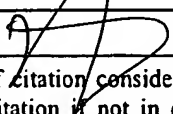
\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<b>INFORMATION DISCLOSURE STATEMENT</b> <b>IN AN APPLICATION</b> (Use several sheets if necessary) PTO Form 1449	Atty Docket No. 112857-319	Application No. 10/092,687
	Applicant Hiroyuki Okuyama et al.	
	Filing Date 03/06/2002	Group 2822

### FOREIGN PATENT DOCUMENTS

Examiner's Initials		Document Number	Publication Date	Country	Class	Subclass	Translation	
							Yes	No
MP	✓	11-075019	03/16/1999	Japan	—	—	—	✓
MP	✓	11-177138	07/02/1999	Japan	—	—	—	✓
MP	✓	11-251253	09/17/1999	Japan	—	—	—	✓
MP	✓	11-312840	11/09/1999	Japan	—	—	—	✓
MP	✓	11-514136	11/30/1999	Japan	—	—	—	✓
MP	✓	11-329745	11/30/1999	Japan	—	—	—	✓
MP	✓	11-346004	12/14/1999	Japan	—	—	—	✓
MP	✓	2000-068593	03/03/2000	Japan	—	—	—	✓
MP	✓	2000-183451	06/30/2000	Japan	—	—	—	✓
MP	✓	2000-223417	08/11/2000	Japan	—	—	—	✓
MP	✓	2000-332343	11/30/2000	Japan	—	—	—	✓
MP	✓	2001-085738	03/30/2001	Japan	—	—	—	✓
MP	✓	2001-184921	07/06/2001	Japan	—	—	—	✓
MP	✓	2001-217503	08/10/2001	Japan	—	—	—	✓
MP	✓	2002-185660	12/12/2002	Japan	—	—	—	✓

Examiner's Initials		OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
MP	✓	Zheleva et al., <i>Pendeo-epitaxy – a new approach for lateral growth of gallium nitride structures</i> , MRS Internet J. Nitride Semicond. Res. 4S1, G3.38 (1999).
MP	✓	Kapolnek et al., <i>Spatial control of InGaN luminescence by MOCVD selective epitaxy</i> , Journal of Crystal Growth, 189/190 (1998) pp. 83-86.

Examiner: 	Date Considered: 9/04
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	